UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/667,491	09/23/2003	Robert Sheffield	57983.000131	1242
21967 HUNTON & W	7590 03/22/201 YILLIAMS LLP	1	EXAM	IINER
INTELLECTUAL PROPERTY DEPARTMENT			VAN, LUAN V	
1900 K STREE SUITE 1200	1, N. W.		ART UNIT	PAPER NUMBER
WASHINGTO	N, DC 20006-1109		1724	
			MAIL DATE	DELIVERY MODE
			03/22/2011	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)	
	10/667,491	SHEFFIELD ET AL.	
Office Action Summary	Examiner	Art Unit	
	LUAN V. VAN	1724	
The MAILING DATE of this communication ap Period for Reply	opears on the cover sheet w	vith the correspondence addres	s
A SHORTENED STATUTORY PERIOD FOR REPLANTING IN STATUTORY PERIOD FOR REPLANTING IN STATUTORY PERIOD FOR REPLANTING IN STATE IN THE MAILING IN STATE IN THE MAILING IN STATE IN THE MAILING IN THE MAILING IN STATE IN THE MAILING IN THE	DATE OF THIS COMMUN. 136(a). In no event, however, may a d will apply and will expire SIX (6) MC te, cause the application to become the complete of the compl	ICATION. Treply be timely filed NTHS from the mailing date of this community NBANDONED (35 U.S.C. § 133).	
Status			
 1) ☐ Responsive to communication(s) filed on 14. 2a) ☐ This action is FINAL. 2b) ☐ The since this application is in condition for allowed closed in accordance with the practice under 	is action is non-final. ance except for formal ma	•	rits is
Disposition of Claims			
4) ☑ Claim(s) 1,2,4-6 and 19-22 is/are pending in 4a) Of the above claim(s) is/are withdres 5) ☐ Claim(s) is/are allowed. 6) ☑ Claim(s) 1, 2, 4-6, and 19-22 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/	awn from consideration.		
Application Papers			
9) The specification is objected to by the Examination The drawing(s) filed on is/are: a) and a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction of the oath or declaration is objected to by the Examination is objected to by the Examination is objected.	ccepted or b) objected to e drawing(s) be held in abeya ction is required if the drawin	ance. See 37 CFR 1.85(a). g(s) is objected to. See 37 CFR 1.	, ,
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of: 1. Certified copies of the priority documer 2. Certified copies of the priority documer 3. Copies of the certified copies of the pri application from the International Bures * See the attached detailed Office action for a list	nts have been received. nts have been received in ority documents have bee au (PCT Rule 17.2(a)).	Application No n received in this National Stag	e
Attachment(s)	_		
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	Paper No	Summary (PTO-413) (s)/Mail Date Informal Patent Application 	

DETAILED ACTION

Response to Amendment

Applicant's amendment of March 14, 2011 does not render the application allowable. Claims 1, 2, 4-6, and 19-22 are pending in the application.

Status of Objections and Rejections

All rejections from the previous office action are maintained.

Claim Rejections - 35 USC § 103

The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.

Claims 1, 2, 4-6, and 19-22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tanaka et al. (US patent 4959507) in view of Nagai et al. (US pub 2002/0155021).

Regarding claims 1 and 21-22, Tanaka et al. teaches a method for forming a bonded ceramic-metal composite substrate, the method comprising the step of: providing a layer of the circuit board 1 having the conductive circuit trace 2 (figure 1) on a surface thereof; and reducing a surface roughness (column 2 lines 23-35) of at least one surface of the conductive circuit trace on the surface of the circuit board layer. The method of Tanaka et al. would improve performance of a signal transmitted via the conductive circuit trace, since the surface roughness of the copper element 2 is reduced. Furthermore, Tanaka et al. teaches that the median surface roughness of the

copper circuit sheet be not greater than 1 μ m, or equivalent to about 254 microinches, and a maximum surface roughness be not greater than 8 μ m, or equivalent to about 387 microinches (column 3 lines 9-12).

Tanaka et al. differs from the instant claim in that the reference does not explicitly teach the smaller roughness of the instant claim.

Nagai et al. teaches that "[1]arge surface roughness of a copper foil results in the skin effect such that the current of electric signal having 1 GHz or more of frequency locally flows only on the surface of a coil. As a result, the impedance increases and the transmission of high-frequency signals is seriously influenced. Fine surface roughness is, therefore, necessary for conductive material used in a high-frequency circuit. The present inventors examined the relationship between the surface roughness and the high-frequency performance and discovered that 2 micrometer or less of surface roughness [or equivalent to about 80 microinches] in terms of the terms of the ten-point average surface-roughness (Rz) attains the desired high-frequency performance. The fine roughness can be provided by means of producing a wrought copper foil or electrodeposited copper foil under appropriate conditions, or chemically or electrolytically polishing the surface of a copper foil" (paragraph 28).

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to have reduced the surface roughness in the copper sheet of Tanaka et al., because a smaller surface roughness would improve the high-frequency performance of the device by reducing the impedance, as taught by Nagai et al. (paragraph 28).

Tanaka et al. is also silent to whether the etching treatment or polishing is performed laterally or transversely with respect to the circuit pattern.

However, since polishing laterally or transversely with respect to the circuit pattern are the only two possible directions, it would have been obvious to one having ordinary skill in the art at the time the invention was made to have tried polishing the circuit pattern of Tanaka et al. either laterally or transversely in order to improve the reliability of the circuit board, as suggested by Tanaka et al. (column 1 lines 43-51). Given these two choices, it would have been obvious to one having ordinary skill in the art to polish either laterally or transversely as these represent a finite number of predictable polishing directions.

Regarding claim 2, Tanaka et al. teaches wherein the step of reducing the surface roughness includes mechanical polishing the at least one surface (column 4 lines 59-64).

Regarding claims 4-5, the grounds of rejection of the instant claims parallel that given above in claim 1.

Regarding claim 6, Tanaka et al. teaches wherein the at least one surface of the conductive circuit trace includes one of a group consisting of: a surface parallel and distal to a surface of the circuit board; a surface parallel and proximal to the surface of the circuit board; and a surface perpendicular to the surface of the circuit board (figure 1).

Regarding claim 19, Tanaka et al. teaches wherein the conductive circuit trace is formed on the surface of the circuit board layer 1 (figure 1).

Regarding claim 20, Tanaka et al. teaches wherein the conductive circuit trace 2 is bonded (i.e., affixed, column 3 lines 56-60) to the surface of the circuit board layer 1.

Response to Arguments

Applicant's arguments filed on March 14, 2011 have been fully considered but they are not persuasive. In the arguments presented on page 8 of the amendment, the applicant disagrees that polishing laterally or transversely are not the only two possible directions because of the possibility of polishing in circular patterns, spiral patterns, etc. In response, the examiner notes that polishing laterally or transversely does not necessarily mean polishing in a linear fashion but simply suggests a direction of polishing. Therefore, even with circular patterns, spiral patterns, etc., one can polish using these patterns in a lateral or transverse direction. With respect to the argument that the Tanaka et al. and Nagai et al. do not teach that claimed smaller surface roughness limitation, this argument has already been addressed by the BPAI decision filed on September 28, 2010.

Conclusion

THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the

Application/Control Number: 10/667,491 Page 6

Art Unit: 1724

shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to LUAN V. VAN whose telephone number is (571)272-8521. The examiner can normally be reached on M-F 9:30-6:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam Nguyen can be reached on 571-272-1342. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Luan V Van/ Primary Examiner, Art Unit 1724 March 17, 2011